

# Test results - VPD ICP-MS

## Methods

The content of trace metals was determined using the vapor phase decomposition inductively coupled mass spectroscopy (VPD-ICP-MS) method.

[Information about the equipment used]

## Additional information

The ICP-MS instrument is calibrated with a blank solution and NIST traceable calibration standards. The ICP-MS system is calibrated before each measurement and can therefore ensure the consistent quality of each individual series of measurements.

The cleanliness of the decomposition chamber and environment is verified with each set of wafers by analyzing wafer controls at the same time as the wafer samples.

[More information about the calibration of the device, cleanroom conditions, and cleanliness]

## Results

**Table 1.** VPD ICP-MS analysis results (LOD: limit of detection)

Element		Result ( $1 \cdot 10^{10}$ atoms/cm <sup>2</sup> )	
		LOD (200 mm)	[Sample name]
Ag	Silver		
Al	Aluminum		
As	Arsenic		
B	Boron		
Ba	Barium		
Be	Beryllium		
Bi	Bismuth		
Ca	Calcium		
Cd	Cadmium		
Ce	Cerium		
Co	Cobalt		
Cr	Chromium		
Cs	Cesium		
Cu	Copper		
Dy	Dysprosium		
Er	Erbium		
Eu	Europium		
Fe	Iron		
Ga	Gallium		
Gd	Gadolinium		
Ge	Germanium		
Hf	Hafnium		
Hg	Mercury		
Ho	Holmium		
In	Indium		
K	Potassium		
La	Lanthanum		

Li	Lithium		
Lu	Lutetium		
Mg	Magnesium		
Mn	Manganese		
Mo	Molybdenum		
Na	Sodium		
Nb	Niobium		
Nd	Neodymium		
Ni	Nickel		
Pb	Lead		
Pr	Praseodymium		
Rb	Rubidium		
Sb	Antimony		
Sc	Scandium		
Se	Selenium		
Sm	Samarium		
Sn	Tin		
Sr	Strontium		
Ta	Tantalum		
Tb	Terbium		
Te	Tellurium		
Th	Thorium		
Ti	Titanium		
Tl	Thallium		
Tm	Thulium		
U	Uranium		
V	Vanadium		
W	Tungsten		
Y	Yttrium		
Yb	Ytterbium		
Zn	Zinc		
Zr	Zirconium		
Au	Gold		
Pd	Palladium		
Pt	Platinum		
Rh	Rhodium		
Ru	Ruthenium		

**End of the test report**